

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
11 March 2004 (11.03.2004)

PCT

(10) International Publication Number
WO 2004/021088 A3

(51) International Patent Classification⁷: G03F 7/38, 7/20

[NL/NL]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

(21) International Application Number:
PCT/IB2003/003663

(74) Agent: COBBEN, Louis, M., H.; Philips Intellectual Property & Standards, Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL).

(22) International Filing Date: 18 August 2003 (18.08.2003)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
02078577.0 30 August 2002 (30.08.2002) EP

(71) Applicant (for all designated States except US): KONINKLIJKE PHILIPS ELECTRONICS N.V. [NL/NL]; Groenewoudseweg 1, NL-5621 BA Eindhoven (NL).

(81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

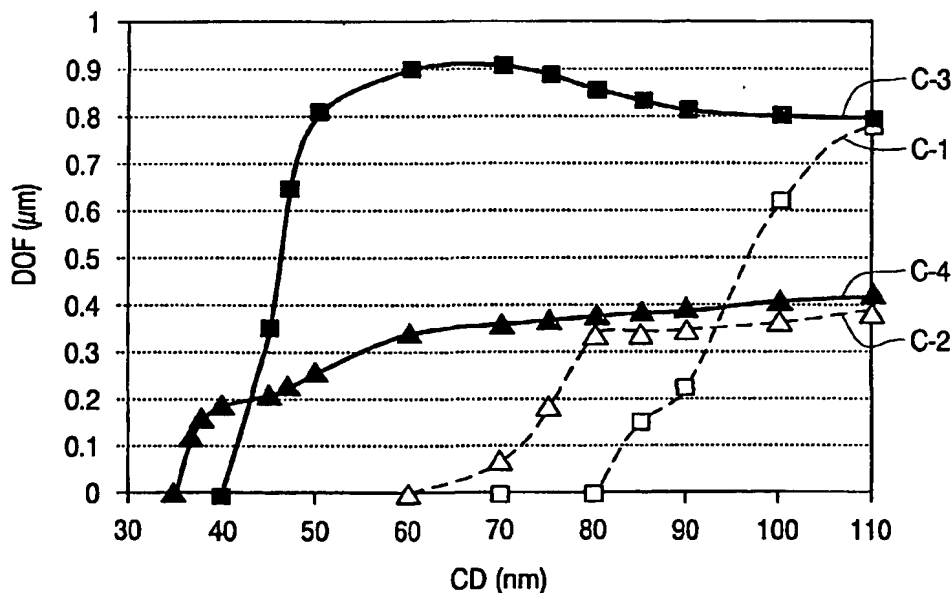
(72) Inventors; and

(75) Inventors/Applicants (for US only): VAN STEENWINKEL, David [BE/BE]; c/o Prof. Holstlaan 6, NL-5656 AA Eindhoven (NL). LAMMERS, Jeroen, H.

(84) Designated States (regional): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

[Continued on next page]

(54) Title: LITHOGRAPHIC METHOD FOR SMALL LINE PRINTING



(57) Abstract: The minimal feature width (CD) of a pattern of device features configured in a substrate layer by means of a lithographic process can be reduced considerably, without reducing process latitudes (DOF), by substantially extending the post-exposure bake step and reducing the exposure dose. By the same measures the isofocal CD can be tuned to the design CD so that for an arbitrary CD process latitudes are enlarged.



Declaration under Rule 4.17:

— as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW, ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE,

DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG)

Published:

— with international search report

(88) Date of publication of the international search report:
2 December 2004

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

INTERNATIONAL SEARCH REPORT

International Application No

PCT/IB 03/03663

A. CLASSIFICATION OF SUBJECT MATTER

IPC 7 G03F7/38 G03F7/20

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

IPC 7 G03F

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the International search (name of data base and, where practical, search terms used)

EPO-Internal, INSPEC, WPI Data, PAJ, IBM-TDB

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	STURTEVANT J ET AL: "Post-exposure bake characteristics of a chemically amplified deep-ultraviolet resist" PROC. SPIE - INT. SOC. OPT. ENG. (USA), PROCEEDINGS OF THE SPIE - THE INTERNATIONAL SOCIETY FOR OPTICAL ENGINEERING, 1992, USA, vol. 1672, 1992, pages 114-124, XP008032436	1,3-12
Y	ISSN: 0277-786X the whole document ----- -/--	2



Further documents are listed in the continuation of box C.



Patent family members are listed in annex.

* Special categories of cited documents:

- *A* document defining the general state of the art which is not considered to be of particular relevance
- *E* earlier document but published on or after the International filing date
- *L* document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)
- *O* document referring to an oral disclosure, use, exhibition or other means
- *P* document published prior to the International filing date but later than the priority date claimed

- *T* later document published after the International filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention
- *X* document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone
- *Y* document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art.
- *G* document member of the same patent family

Date of the actual completion of the International search

5 August 2004

Date of mailing of the International search report

01/09/2004

Name and mailing address of the ISA

European Patent Office, P.B. 5818 Patentlaan 2
NL - 2280 HV Rijswijk
Tel. (+31-70) 340-2040, Tx. 31 651 epo nl,
Fax: (+31-70) 340-3016

Authorized officer

Haenisch, U

INTERNATIONAL SEARCH REPORT

International Application No

PCT/IB 03/03663

C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT

Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
Y	ANONYMOUS: "Novel method to generate shallow sloped vias and contacts" RESEARCH DISCLOSURE, KENNETH MASON PUBLICATIONS, HAMPSHIRE, GB, vol. 286, no. 55, February 1988 (1988-02), XP007112223 ISSN: 0374-4353 the whole document	2
A	ROCQUE J M ET AL: "UVIII-positive chemically amplified resist optimization" PROC. SPIE - INT. SOC. OPT. ENG. (USA), PROCEEDINGS OF THE SPIE - THE INTERNATIONAL SOCIETY FOR OPTICAL ENGINEERING, 1998, SPIE-INT. SOC. OPT. ENG, USA, vol. 3331, 1998, pages 487-495, XP002286921 ISSN: 0277-786X	
A	CAPODIECI L ET AL: "Novel methodology for postexposure bake calibration and optimization based on electrical linewidth measurement and process metamodeling" J. VAC. SCI. TECHNOL. B, MICROELECTRON. NANOMETER STRUCT. (USA), JOURNAL OF VACUUM SCIENCE & TECHNOLOGY B (MICROELECTRONICS AND NANOMETER STRUCTURES), NOV.-DEC. 1998, AIP FOR AMERICAN VACUUM SOC, USA, vol. 16, no. 6, 1998, pages 3752-3758, XP002286922 ISSN: 0734-211X	
A	DOBISZ E A ET AL: "Electron-beam nanolithography, acid diffusion, and chemical kinetics in SAL-601" J. VAC. SCI. TECHNOL. B, MICROELECTRON. NANOMETER STRUCT. (USA), JOURNAL OF VACUUM SCIENCE & TECHNOLOGY B (MICROELECTRONICS AND NANOMETER STRUCTURES), NOV.-DEC. 1998, AIP FOR AMERICAN VACUUM SOC, USA, vol. 16, no. 6, 1998, pages 3773-3778, XP002286923 ISSN: 0734-211X	